Optical-Lithography Ma-P 1210 Processing

Rinse and dry the substrate

Spin: 3000 rpm, 30s

Prebake: 100 °C in oven, 15 min

Exposure: 8-10 s

Prebake (optional) : 90°C, 2 min

Develop: ma-D 531 , 20 s

Hardbake (optional): 100°C